

## IEEE SW Test Workshop

### Semiconductor Wafer Test Workshop

June 9 - 12, 2013 | San Diego, California

# "Sparking" Challenges: AC high voltage wafer test



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T.I.P.S. Messtechnik

### **Overview**

#### Devices under test

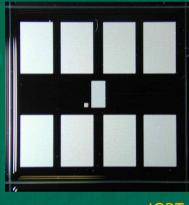
- Power switches (IGBT, MOSFET, Diodes; Si, SiC, GaN,...)
- High voltage communication devices

#### Test requirements

- AC wafer level testing up to 10kV
- low current
- 50/60 Hz

#### Test limitations

- Flash-over strength of probe card / DUT
- Voltage, pressure, device geometry



**IGBT** 



### **Objectives**

- Outline Flash-over theory
  - Gas discharge mechanisms
  - Voltage strength vs. pressure
  - Field homogeneity
  - Surface discharges
- Characterize limitations of test equipment
  - Measured voltage strength
  - Predictability of voltage strength
- Guidelines for probe card design (T.I.P.S.)
  Recommendations for test development
  - Safe flash-over distances
  - Considerations for AC test design



### Flash-over theory

#### **Generation mechanism**

#### Start condition

- Presence of start electron
- Ionization by UV light/cosmic radiation
- Stochastic nature

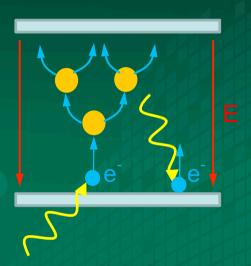
#### Electron avalanche

- Electron accelerated to ionization energy
- Collision → new electrons → avalanche
- Recombination → photons → new start electron on cathode

### Self-sustaining discharge if

- More new electrons than recombinations
- Every avalanche triggers at least one new = Ignition condition





### Paschen law

#### Empirical

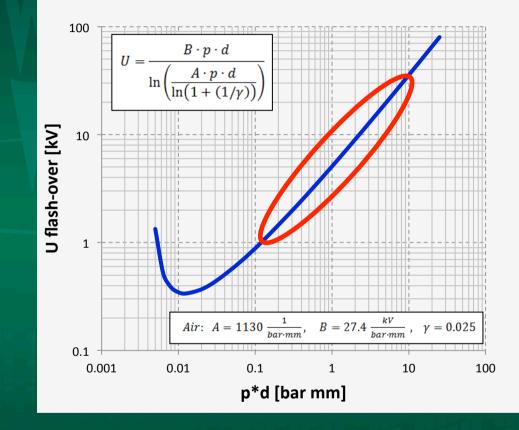
- Homogenous field
- Function of (p\*d)
- depends on gas type
- electrode material

#### . Use

- General behavior
- Estimate pressure

### Applicability

- Limited (homogeneity)
- No data for common probe materials





### Flash-over theory

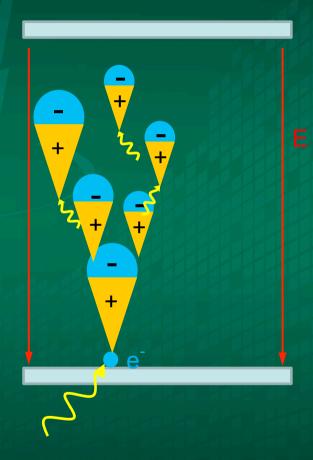
Streamer mechanism

#### . Streamer

- Start in high field strength
- Fast growth (during one avalanche)
- Can traverse low field regions
- Self propagating

### Space charge

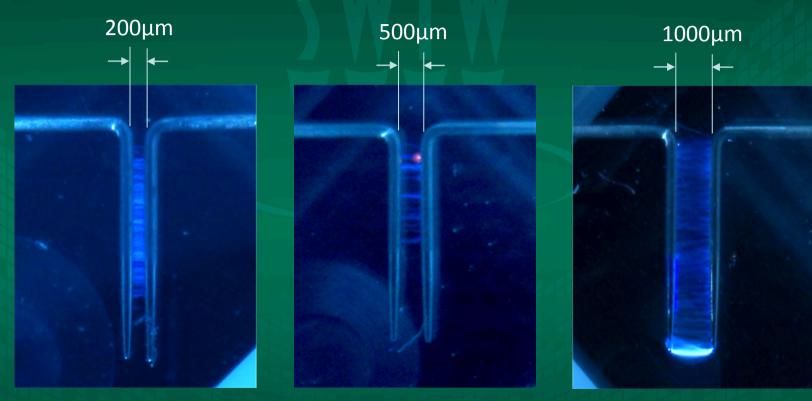
- lons slower than electrons
- Electron cloud
- Electric field enhancement





## Flash-over: atmospheric pressure

p = 1 bar absolute

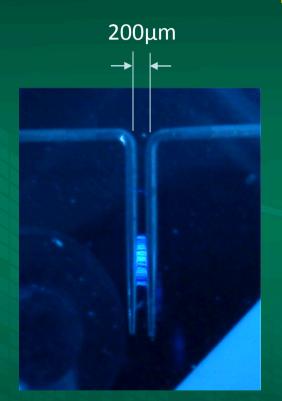


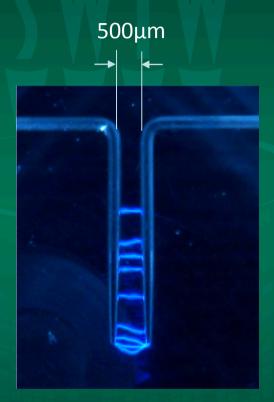
randomly distributed streamers: many short (nanosecond) discharges, UV emission, not audible



## Flash-over medium pressure

p = 4 bar absolute





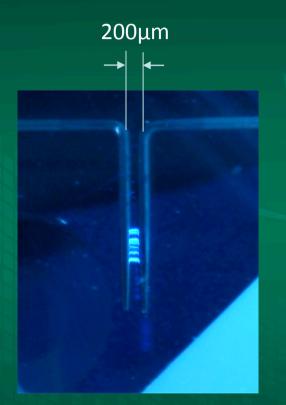


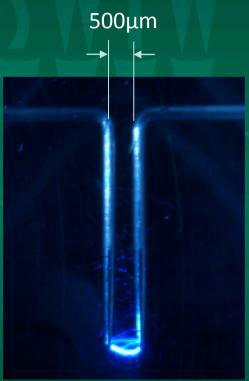
increasing pressure -> transition from streamer to spark

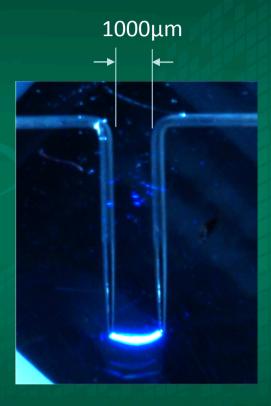


# Flash-over high pressure

p = 7 bar absolute







spark discharge only at probe tip: intense visible light emission, audible



## **Experimental data processing**

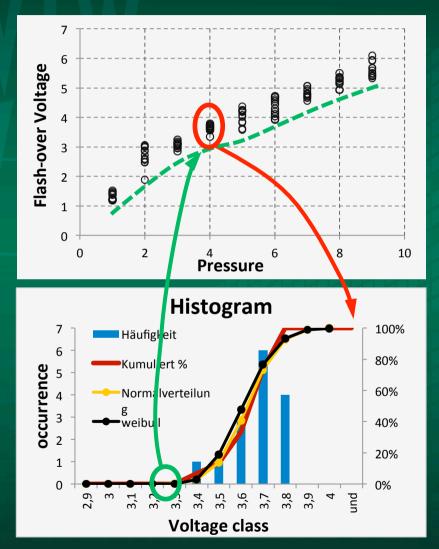
#### Statistical data analysis

- Histogram, cumulated
- Weibull approximation
- Amount of data limited,
  limited accuracy

#### . Conclusion

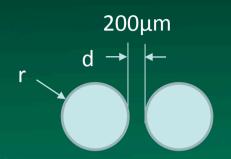
- Withstand voltage\*:flashover probability very low
- Keep safety margin!

\*limit for flashovers

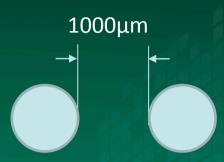


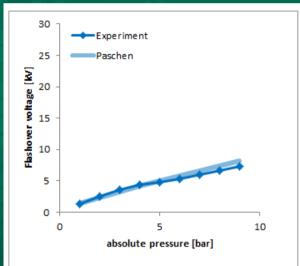


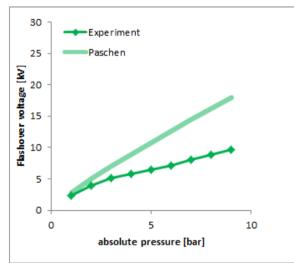
## Flash-over voltage: experiment

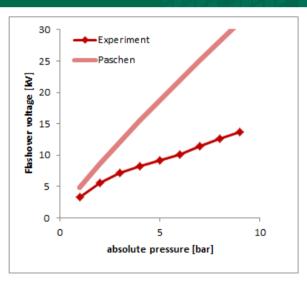












... good correlation with Paschen law only for homogenous electric field

tungsten probes 10 mil diameter



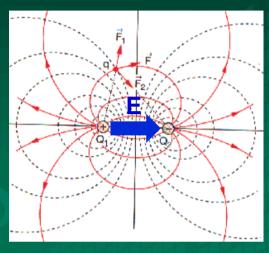
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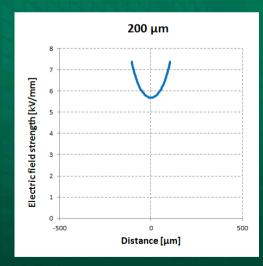
## **Electric Field - analytical**

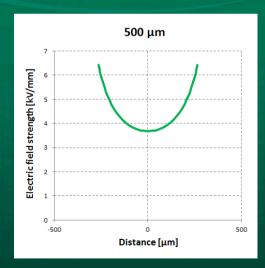
### Parallel cylindrical conductors

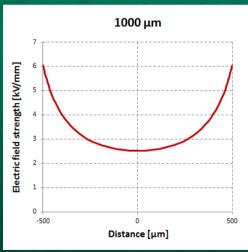
- Analytical expression for field strength
- cylinder radius r, center distance c
- E= f (r,c,U)

$$E(x) = U \cdot \frac{1/(\frac{a}{2} - x) + 1/(\frac{a}{2} + x)}{(\frac{a}{2} + \frac{c}{2} - r)/(\frac{a}{2} + \frac{c}{2} + r)} \qquad a = 2\sqrt{\frac{c^{2}}{4} - r^{2}}$$





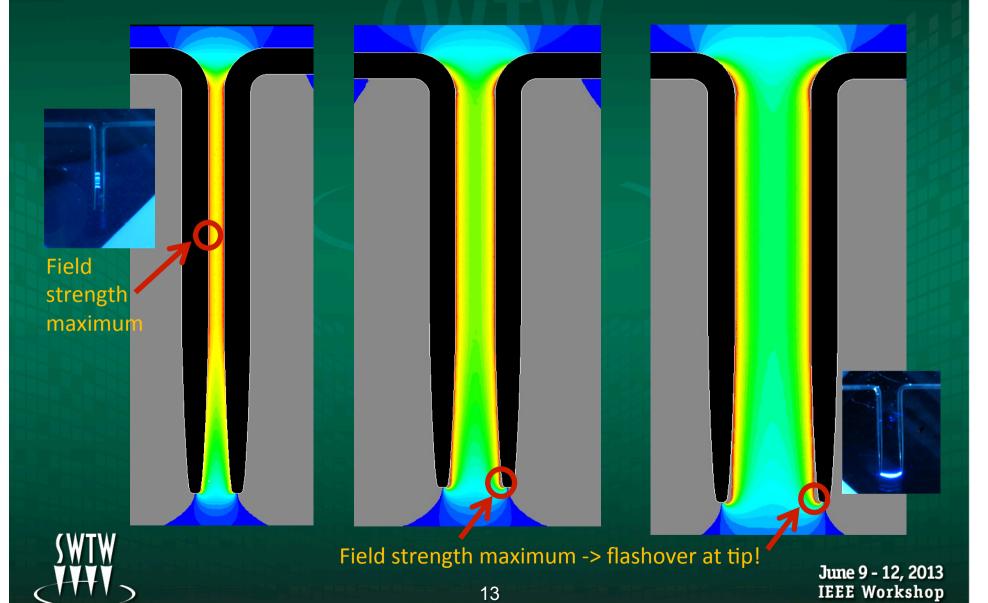




field strength calculated for experiment flashover voltage (at pressure = 1 bar)



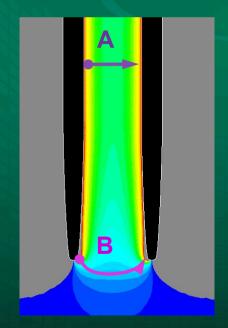
### **Electric field - FEM**

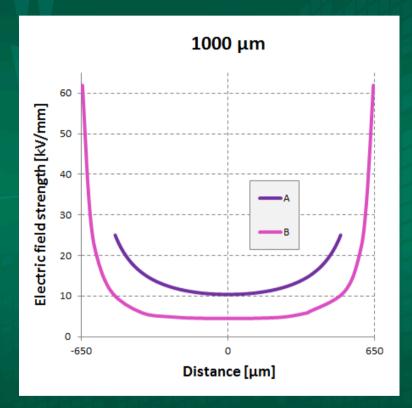


## **Electric field inhomogeneity**

#### Field concentration

- small radius at probe tip
- local field strength maximum
- despite lower field in middle
- discharge along path B observed





field strength calculated using flashover voltage (at pressure = 9 bar) from experiment



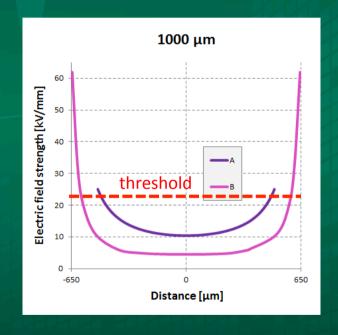
## Streamer propagation

### high field strength

- number of electrons grows exponentially along field line
- if field stronger than threshold

### low field strength

- if number of electrons N > N<sub>krit</sub>
- enough charge accumulated
- charge enhances field
- propagation continues





# Wafer contacted: a different story...

#### · FEM

- Device geometry becomes dominant

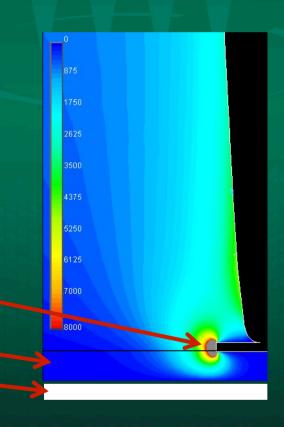
#### . Conclusion

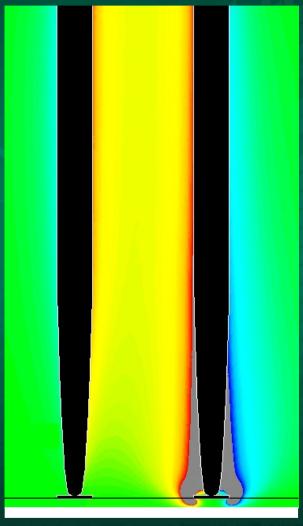
device sets the limit,
 not the probe card

Field strength many times higher than on uncontacted probes

Dielectric layer

Wafer

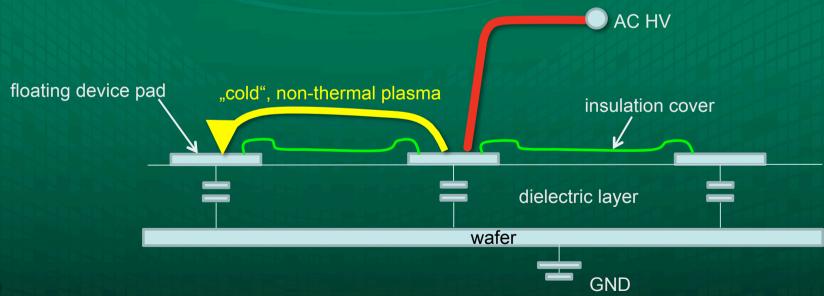






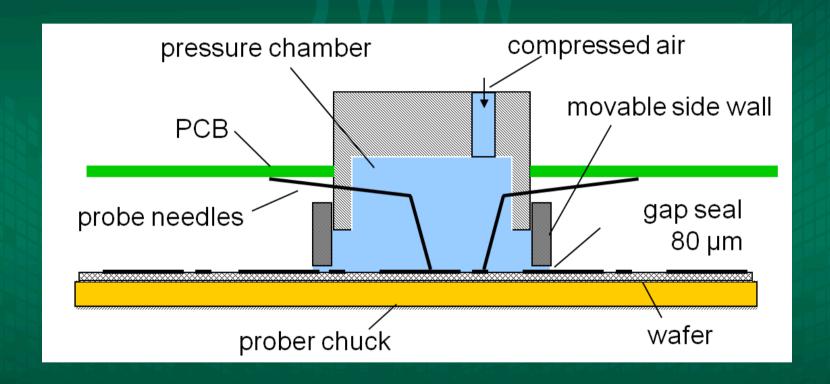
## AC testing additional difficulties

- Capacitively coupled discharge path to neighboring devices
  - depending on specific capacity and geometry
  - Quasi-continuous partial discharge at AC frequency
  - "plasma etching" of wafer surface possible damage to e.g. polyimide insulation covers





# Luftpolster probe card





## **Luftpolster Probe card**

#### Pressure chamber

- CDA supply up to 8 bar
- Chamber pressure up to 6 bar
- Lab tests up to 10 bar

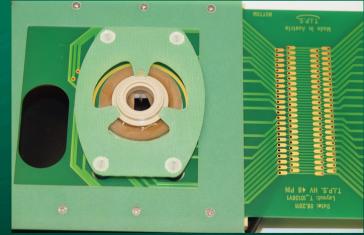
### Air bearing seal

- Seal ring hovering
- No-contact operation

#### . Features

- Optical window for alignment
- can be operated on manual and automated probers
- only one additional CDA line required







### Summary

#### Test equipment:

- Simple design rules for HV probe card design confirmed
- AC Flash-over strength was characterized
- Measured behavior aligns well with theory
- Probe card does not set the limits: flashovers occur between DUT terminals
- DUT geometry becomes dominant may require experimental verification

### Additional AC test specific effects:

- Consider capacitive coupling to neighboring devices
- Partial discharge may degrade device surface

**Conclusion: You better know your field!** 



### Acknowledgements

### Named and unnamed contributing to this work:

- our staff at TIPS Messtechnik
- customers that remain anonymous...

#### . References:

- A. Küchler, Hochspannungstechnik, VDI 2009
- C. Louste et al, Sliding discharge in air, Journal of electrostatics 2005
- S. Boenisch, ESD at small distances and voltages, TU Berlin 2004

